Advance in Machine Learning

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Deadline for manuscript submissions:
closed (15 October 2021)

Message from the Guest Editors

Machine learning is filling the gaps between theory and practice and helps to change virtually every aspect of modern lives. Today, advance in machine learning algorithms accomplishes tasks to solving real-world problems that until recently only expert humans could perform.

In this Special Issue, we seek research and case studies that demonstrate the application of machine learning to support applied scientific research, in any area of science and technology. Example topics include (but are not limited to) the following topics applied to machine learning:

- New machine learning algorithms
- New optimization techniques
- Distributed machine learning systems and architectures
- New applications on real-time/big data analytics
- Intelligent applications
- Quantum machine learning
- Data and code integration
- Visualization of modern systems and networks
- High-throughput data analysis
- Comparison and alignment methods

Special Issue

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Message from the Editor-in-Chief

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